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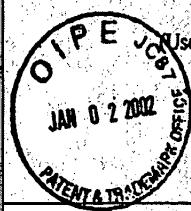
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LIST OF DOCUMENTS CITED BY APPLICANT

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Applicants: Luckovsky et al.

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U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate

FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Subclass	Translation Yes No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

QW	1. Gordon et al., "Chemical Vapor Deposition and Properties of Amorphous Aluminum Oxide Films," Material Research Society Symposium Proceedings, 446, December 2-4, 1996, 383-388.
QW	2. Hauser et al., "Characterization of Ultra-Thin Oxides Using Electrical C-V and I-V Measurements," Characterization and Metrology for ULSI Technology: 1998 International Conference, CP449, 235-239.
QW	3. Luckovsky et al., "Minimization of Mechanical and Chemical Strain at Dielectric-Semiconductor and Internal Dielectric Interfaces in Stacked Gate Dielectrics for Advanced CMOS Devices," Characterization and Metrology for ULSI Technology: 2000 International Conference, CP550, 154-158.
QW	4. Rayner et al., "Spectroscopic Evidence for a Network Structure in Plasma-Deposited Ta ₂ O ₅ Films for Microelectronic Applications," Characterization and Metrology for ULSI Technology: 2000 International Conference, CP550, June 26-29, 2000, 149-153.
QW	5. Schroder, "Oxide and Interface Trapped Charges, Oxide Integrity," Semiconductor Material and Device Characterization, Second Edition, 1998, 337-419.
QW	6. Vickridge et al., "Spaces: A PC Implementation of the Stochastic Theory of Energy Loss for Narrow-Resonance Depth Profiling," Nuclear Instruments and Methods in Physics Research, B45, 1990 6-11. Presented at Proceedings of the Ninth International Conference on Ion Beam Analysis, June 26-30, 1989.

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